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2P/IFW

Attorney Docket No.: 28955.1048

## IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

Serial No. 10/531,208

Confirmation No. 6424

In re Application of

MITSURU UEDA, *et al.*

Art Unit: 1795

Filed: April 14, 2005

Examiner: Sin J. Lee

For: PHOTORESIST BASE MATERIAL, METHOD FOR PURIFICATION THEREOF,  
AND PHOTORESIST COMPOSITIONS

US PATENT AND TRADEMARK OFFICE  
Customer Service Window – Mail Stop AF  
Randolph Building  
401 Dulany Street  
Alexandria, Virginia 22313-1450

AMENDMENT

In response to the Office Action mailed June 9, 2009, please amend the above-identified  
patent application as follows: